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Applicant: VAN SANTEN et al.

Appn. No. 10/743,271

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Examiner: Unknown Group Art Unit: 2851

U.S. PATENT DOCUMENTS

Examiner's Initials	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
HN	AR 6,560,032	05/2003	HATANO	359	656	
	BR 6,603,130	08/2003	BISSCHOPS et al.	250	492.1	
	CR 6,633,365	10/2003	SUENAGA	355	53	
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	GR 2004/0075895 A1	04/2004	LIN	359	380	
HN	HR 2004/0109237 A1	06/2004	EPPEL et al.			
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	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclosed	No
HN	JR JP 07-220990	08/1995	JAPAN	FUKUDA et al.		X		
	KR JP 10-228661	08/1998	JAPAN	KUROKAWA		X		
	LR JP 10-255319	09/1998	JAPAN	SUENAGA et al.		X		
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	PR JP 07-132262	05/1995	JAPAN	HIRAKAWA et al.		X		
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	RR WO 2004/019128	03/2004	PCT	OMURA et al.		X		X
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HN	VR	B.J. LIN, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002						
	WR	B.J. LIN, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997						
	XR	B.J. LIN, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269						
	YR	G.W.W. STEVENS, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72						
	ZR	S. OWA et al., "Immersion Lithography: its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003						
HN	AAR	S. OWA et al., "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)						

Examiner	H. Nguyen	Date Considered:	6/13/05
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.			